

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)	Docket No.:	020732-97.668
)		(7493)
)		
Applicants:	RATH, Melissa K., et al.)	Conf. No.:	4823
)		
Application No.:	10/792,038)	Art Unit:	1752
)		
Date Filed:	March 3, 2004)	Examiner:	LE, Hoa Van
)		
Title:	COMPOSITION AND PROCESS FOR)	Customer No.:	24239
	POST-ETCH REMOVAL OF)		
	PHOTORESIST AND/OR)		
	SACRIFICIAL ANTI-REFLECTIVE)		
	MATERIAL DEPOSITED ON A)		
	SUBSTRATE)		

**AMENDMENT RESPONDING TO OCTOBER 19, 2007 OFFICE ACTION AND REQUEST
FOR A ONE-MONTH EXTENSION UNDER 37 CFR §1.136(a) IN UNITED STATES
PATENT APPLICATION NO. 10/792,038**

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This responds to the October 19, 2007 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the October 19, 2007 Office Action are set out in the **Section II (Remarks)** hereof.